Appl. No. 10/743,985 Amdt. dated August 24, 2005 Reply to Office action of July 27, 2005

REMARKS

The action requires applicants to elect a species from the following groups: (1) SOI device having gate with oxygen or halogen ions and an additional gate region covering all implants (claims 11-19); (2) SOI device on a substrate on an Si wafer with semiconductor layer as part of the substrate and oxygen ions in the substrate forming implants in the gate oxide (claims 20-26); or (3) SOI device on a semiconductor wafer with halogen implants in the gate oxide.

Applicants elect species (1), directed to an SOI device having gate with oxygen or halogen ions and an additional gate region covering all implants (claims 11-19). This election of claim is made without traverse.

Claim 11 is amended to make the terminology consistent within the claim.

In view of the foregoing amendments and remarks, Applicant submits that this application is in condition for allowance. Early notification to that effect is respectfully requested.

The Assistant Commissioner for Patents is hereby authorized to charge any additional fees or credit any excess payment that may be associated with this communication to deposit account 04-1679.

Dated: August 24, 2000

Respectfully submitted,

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